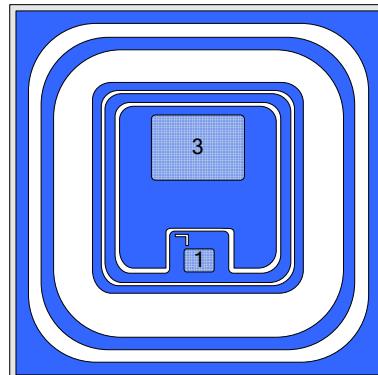


3VD212600YL HIGH VOLTAGE MOSFET CHIPS

DESCRIPTION

- 3VD212600YL is a High voltage N-Channel enhancement mode power MOS-FET chip fabricated in advanced silicon epitaxial planar technology.
- Advanced termination scheme to provide enhanced voltage-blocking capability.
- Avalanche Energy Specified
- Source-to-Drain Diode Recovery Time Comparable to a Discrete Fast Recovery Diode
- The chips may packaged in TO-251 type and the typical equivalent product is 1N60A.
- The packaged product is widely used in AC-DC power suppliers, DC-DC converters and H-bridge PWM motor drivers.
- Die size: 2.12mm*2.02mm.
- Chip Thickness: $300\pm20\mu\text{m}$.
- Top metal: Al, Backside Metal: Ag.



PAD1:GATE PAD3:SOURCE

CHIP TOPOGRAPHY

ABSOLUTE MAXIMUM RATINGS ($T_{\text{amb}}=25^\circ\text{C}$)

Parameter	Symbol	Ratings	Unit
Drain-Source Voltage	V_{DS}	600	V
Gate-Source Voltage	V_{GS}	± 30	V
Drain Current	I_D	1.0	A
Power Dissipation(TO-251 Package)	P_D	28	W
Operation Junction Temperature	T_J	-55~+150	$^\circ\text{C}$
Storage Temperature	T_{stg}	-55~+150	$^\circ\text{C}$

ELECTRICAL CHARACTERISTICS ($T_{\text{amb}}=25^\circ\text{C}$)

Parameter	Symbol	Test conditions	Min	Typ	Max	Unit
Drain -Source Breakdown Voltage	BV_{DSS}	$V_{GS}=0\text{V}$, $I_D=250\mu\text{A}$	600	-	-	V
Gate Threshold Voltage	V_{TH}	$V_{GS}=V_{DS}$, $I_D=250\mu\text{A}$	2.0	-	4.0	V
Drain-Source Leakage Current	I_{DSS}	$V_{DS}=600\text{V}$, $V_{GS}=0\text{V}$	-	-	1.0	μA
Static Drain- Source On State Resistance	$R_{DS(\text{on})}$	$V_{GS}=10\text{V}$, $I_D=0.5\text{A}$	-	8.1	8.5	Ω
Gate-Source Leakage Current	I_{GSS}	$V_{GS}=\pm 30\text{V}$, $V_{DS}=0\text{V}$	-	-	± 100	nA
Source-Drain Diode Forward On Voltage	V_{FSD}	$I_S=1.0\text{A}$, $V_{GS}=0\text{V}$	-	-	1.4	V